

Veeco's Microetch™ technology both etches and deposits in a single process chamber.

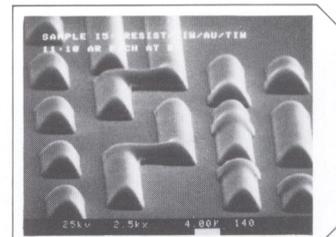
Microetch™ Dual Ion Source Systems etch and clean substrates and deposit precision thin film materials simultaneously or sequentially without exposing the substrate to atmosphere. In addition, processing is done at the lowest possible pressure.

Unlike conventional diode sputtering systems, Microetch™ Systems let you maintain low substrate temperatures while controlling the angle of deposition. The result is the best combination of film adhesion without radiation damage.

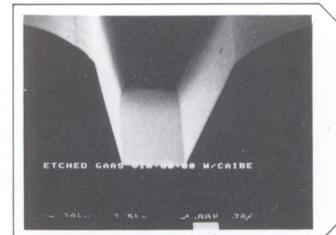
Veeco designs and manufactures comprehensive systems, and offers extensive application and lab service support. To discuss your application requirements, call or write: Veeco Instruments Inc., Terminal Drive, Plainview, NY 11803. 516-349-8300 or 800-833-2648.



**The leader
in ion beam etch
and deposition.**

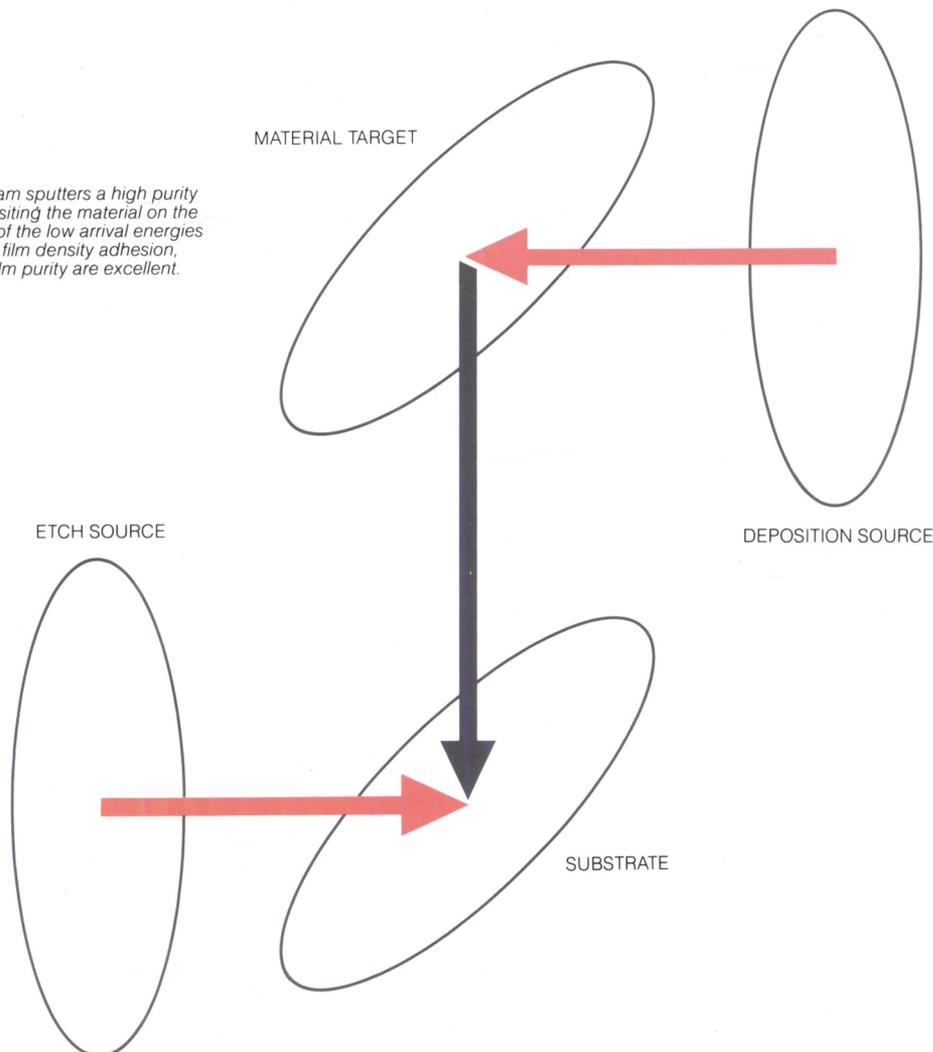


Gold metalization taper etch for GaAs high frequency devices using ion beam etching



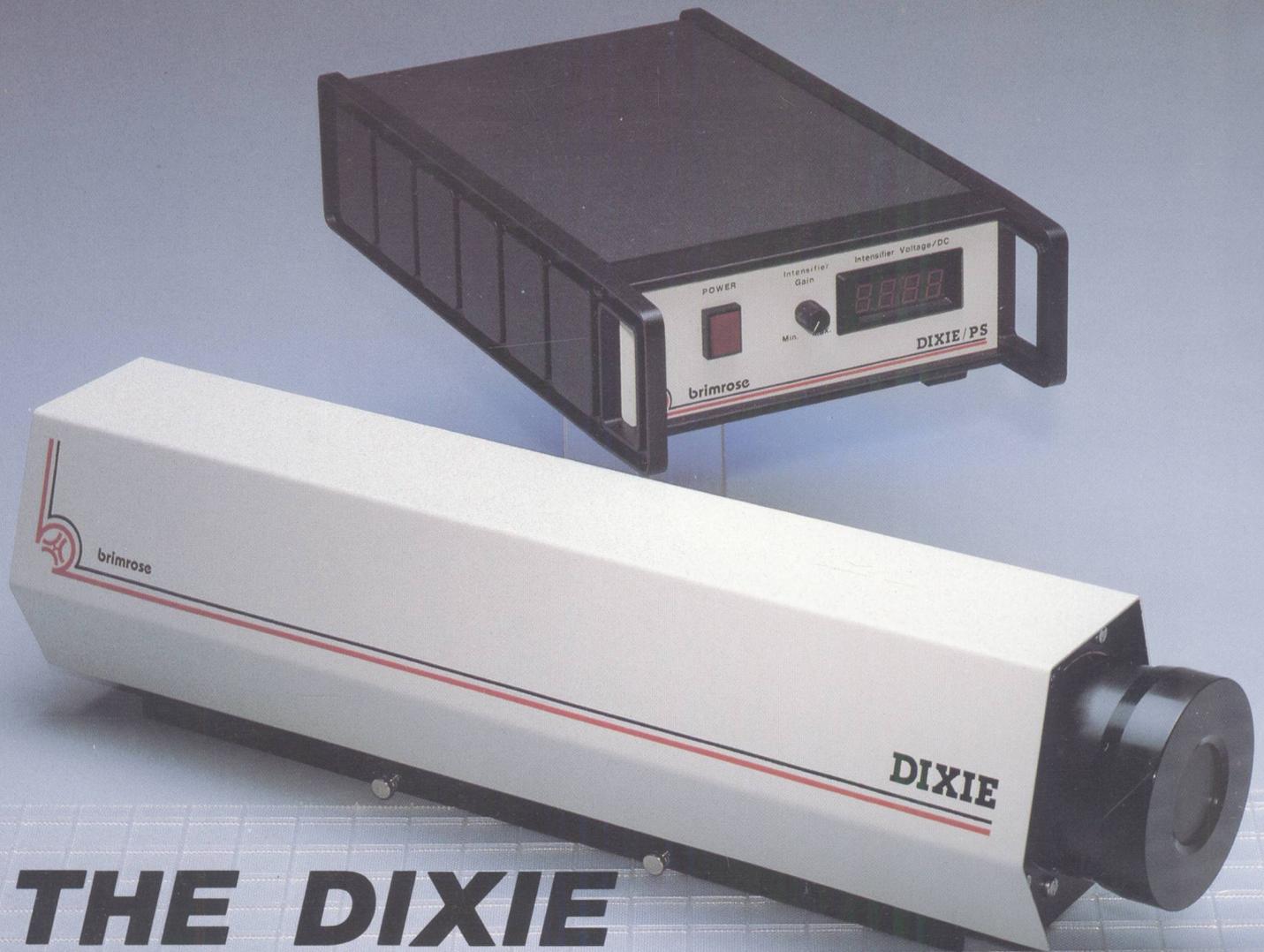
Etched GaAs VIA 20 micron deep hole using chemically assisted ion beam etching

The collimated ion beam sputters a high purity target, precisely depositing the material on the substrate. As a result of the low arrival energies of deposited material, film density adhesion, alloy replication and film purity are excellent.



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TAKE THE "WAIT AND SEE" OUT OF YOUR X-RAY WORK.



THE DIXIE

DIGITAL INTENSITY X-RAY IMAGE ENHANCER
system brings real time x-ray imaging to your lab. With a full 40mm diameter input window and up to 200,000 gain. You can see immediately what film gives you later.

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